

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (original): A method of manufacturing liquid crystal display device comprising the steps of:

    forming an organic material film having projections and depressions, using a photo-embossing material, on an insulating film on an underlying electrode in a thin-film transistor of an active-matrix liquid crystal display device;

    exposing said insulating film in a contact-hole-forming-area by reducing a thickness of said organic material film by a dry etching to said organic material film; and

    forming a contact hole by a dry etching to the exposed insulating film.

Claim 2 (original): A method as claimed in claim 1, further comprising the steps of:

    exposing said underlying electrode in forming said contact hole; and

    contacting the exposed underlying electrode with a reflective electrode by forming said reflective electrode on the resulting structure.

Claim 3 (currently amended): A method as claimed in claim 1  
~~or 2~~, wherein said photo-embossing material is a material  
patternable by an exposing step and a baking step.

Claim 4 (original): A method as claimed in claim 3, wherein  
said organic material film is formed by exposing and baking said  
photo-embossing material in forming said organic material film.

Claim 5 (original): A method as claimed in claim 4, wherein a  
halftone mask or a diffraction mask is used in exposing.

Claim 6 (currently amended): A method as claimed in ~~any one~~  
~~of claims 1-to-5~~, wherein the dry processes are performed from  
the step of forming said organic material film to the step of  
forming said contact hole.

Claim 7. (currently amended): A method as claimed in ~~any one~~  
~~of claims 1-to-6~~, wherein the step of exposing said insulating  
film and the step of forming said contact hole are performed in  
a single apparatus.

Claim 8 (currently amended): A method as claimed in ~~any one~~  
~~of claims 1-~~to~~-7~~, wherein a dry etching process in the step of  
exposing said insulating film is performed in an Inductively  
Coupled Plasma mode or a reactive ion etching mode.

Claim 9 (currently amended): A method as claimed in ~~any one~~  
~~of claims 1-~~to~~-8~~, wherein said liquid crystal display device is  
a reflective type of liquid crystal display device or a  
transflective type of liquid crystal display device.